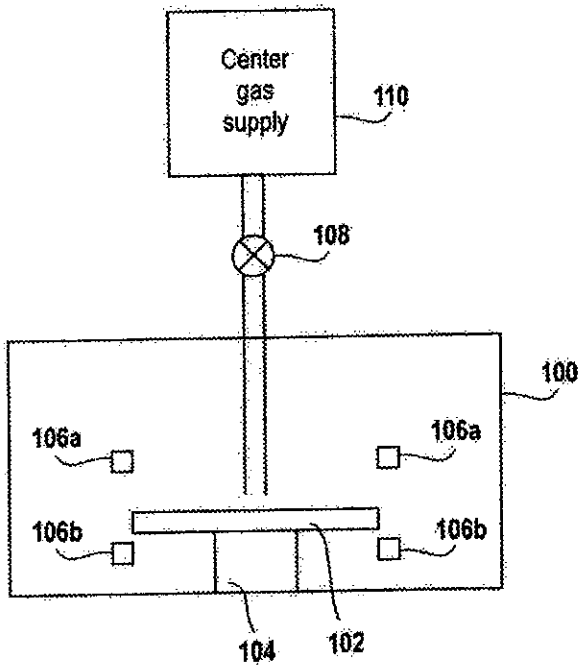


FIG. 1

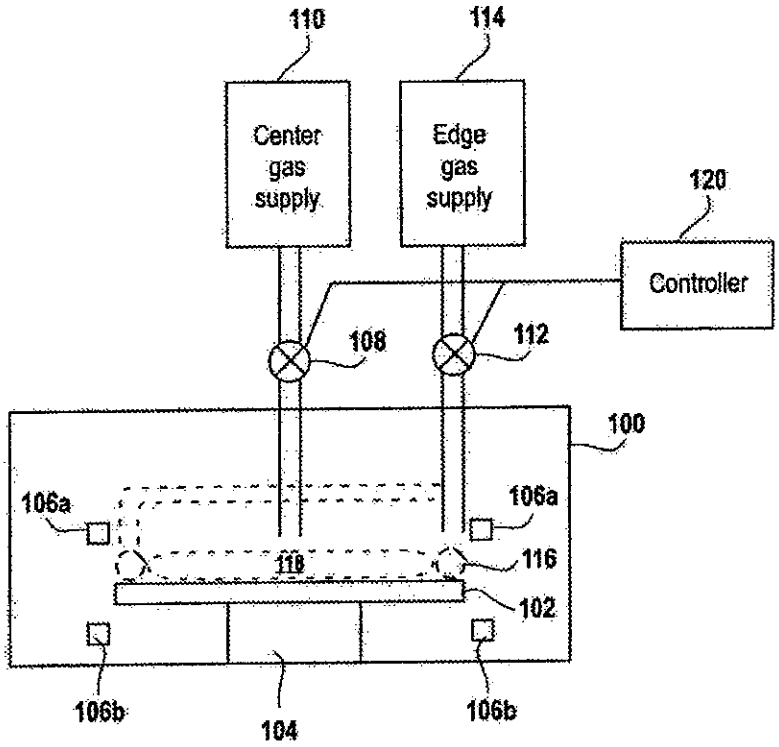

110
114
Center gas supply
Edge gas supply
120
Controller
108
112
100
106a
106a
118
116
102
106b
104
106b

FIG. 2

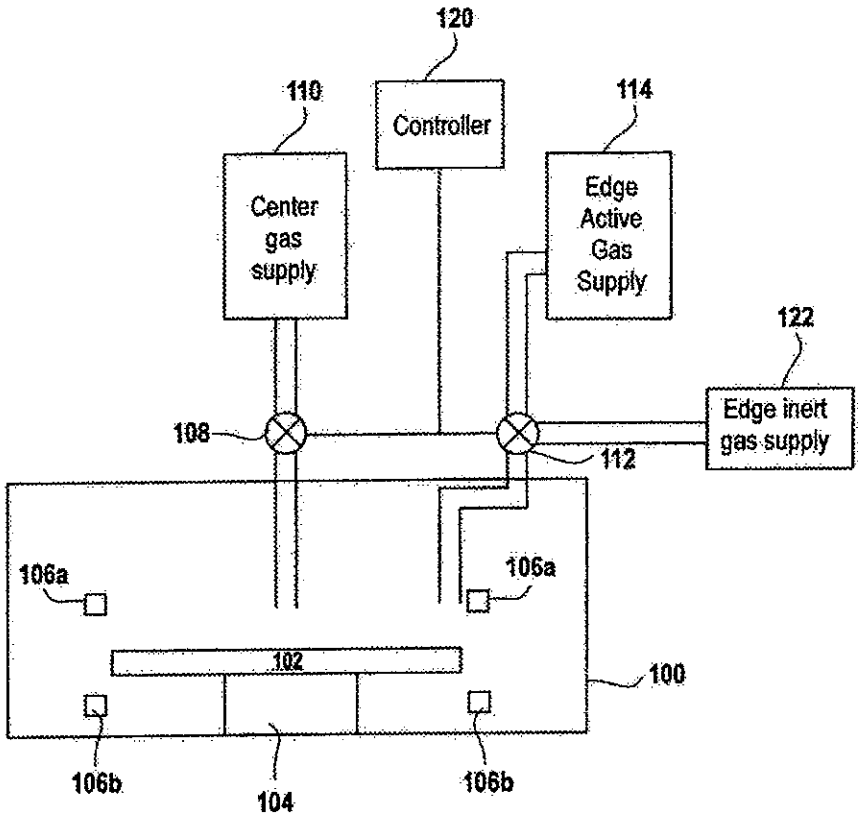

120
110
Controller
114
Center gas supply
Edge Active Gas Supply
122
Edge inert gas supply
108
112
106a
106a
102
100
106b
104
106b

FIG. 3

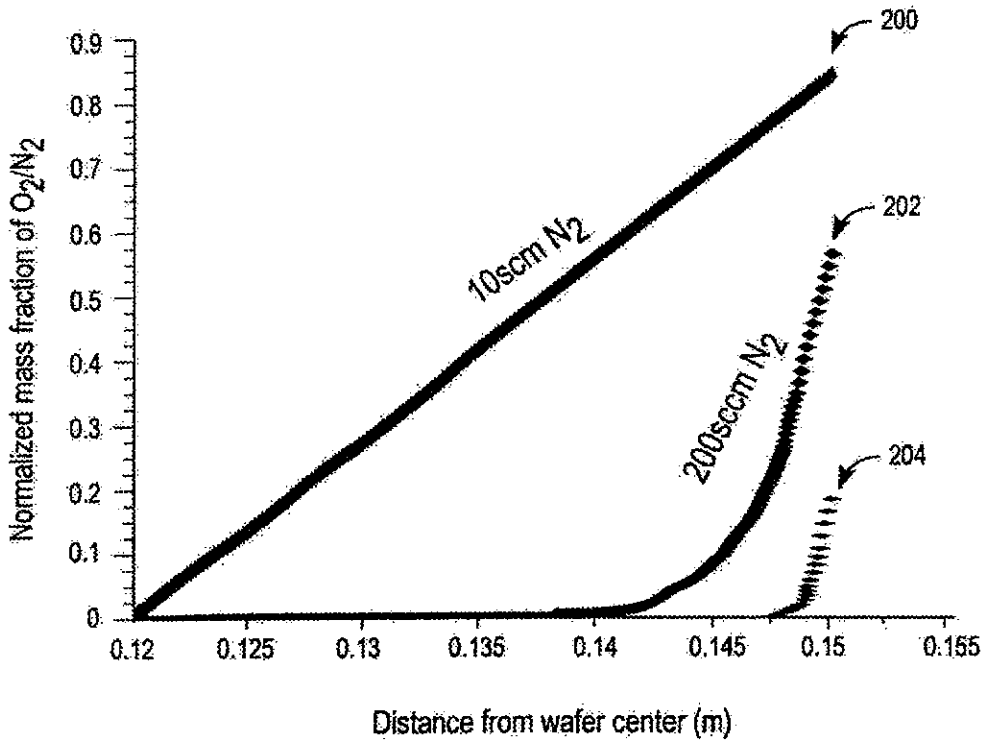

200
202
204
10sccm N_2
200sccm N_2
Normalized mass fraction of O_2/N_2
0.9
0.8
0.7
0.6
0.5
0.4
0.3
0.2
0.1
0
0.12
0.125
0.13
0.135
0.14
0.145
0.15
0.155
Distance from wafer center (m)

FIG. 4

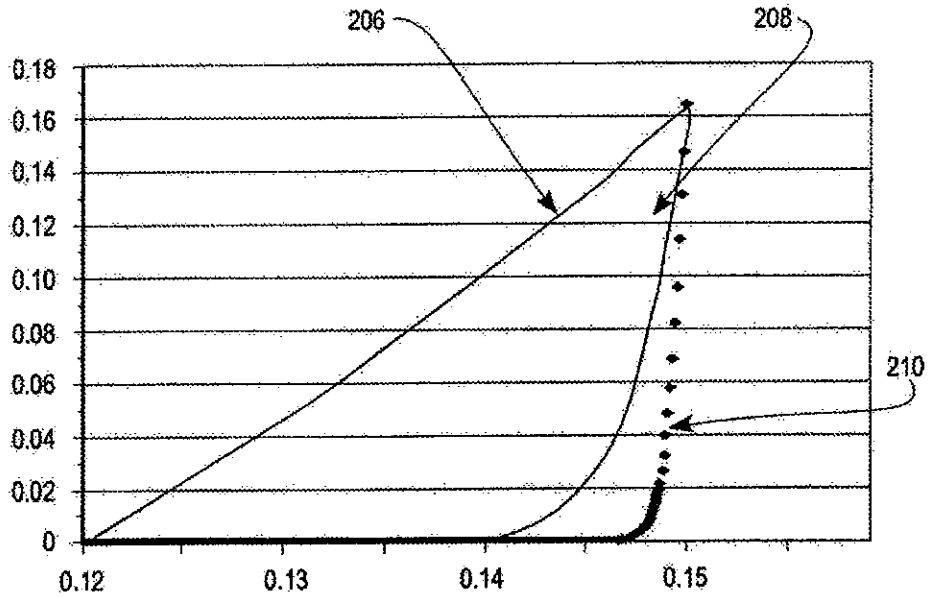


FIG. 5

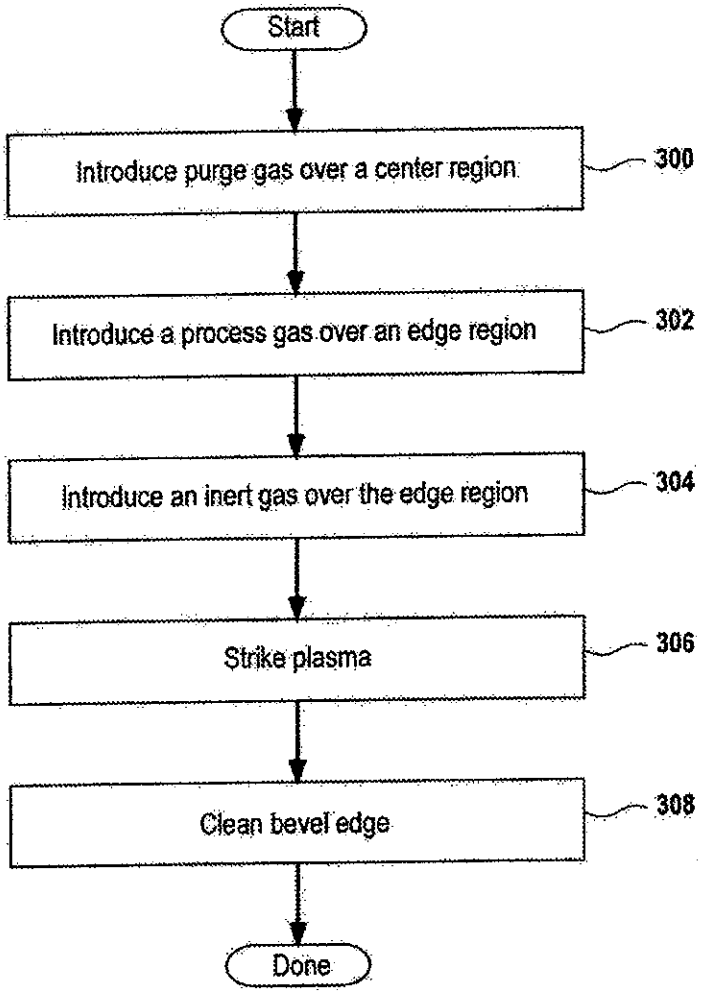

Start
Introduce purge gas over a center region
300
Introduce a process gas over an edge region
302
Introduce an inert gas over the edge region
304
Strike plasma
306
Clean bevel edge
308
Done

FIG. 6